-- SUMMARY OF THE INVENTION

Page 12, before line 1, insert the section heading:

-- DETAILED DESCRIPTION

IN THE CLAIMS

Please cancel Claims 1-13 without prejudice or disclaimer and add the following new Claims 14-22.

with a layer of aluminium oxynitride deposited by gas-phase pyrolysis, the thickness and refractive index characteristics thereof being selected so as to attenuate the reflected colours produced by an oxide layer providing the glazing with low-emission and/or solar protection properties, said layer being deposited onto the aluminium oxynitride layer.

15. (New) Glazing according to Claim 1, and including at least one of the following features(A) through (D);

(A) wherein the constituent elements of the aluminium oxynitride layer are respectively in the following atomic proportions:

Al from 40 to 50%

N from 20 to 50%

O from 10 to 60%;

- (B) wherein the refractive index of the aluminium oxynitride layer is in the range of between 1.6 and 1.8;
- (C) wherein the thickness of the aluminium oxynitride layer is in the range of between 500 and 900 angströms; and

A CONTRACTOR

wherein the oxide layer providing the low-emission and/or solar protection properties is a layer based on doped tin oxide.

- 16. (New) Glazing according to Claim 15 and including at least two of the features (A) through (D).
- 17. (New) Glazing according to Claim 15 and including all of the features (A) through (D).
- 18. (New) Glazing according to Claim 17 wherein:
 the constituent elements of the aluminium oxynitride
 layer are respectively in the following atomic
 proportions:

Al from 45 to 50% N from 22 to 30% O from 20 to 27%;

the refractive index of the aluminium oxynitride layer is in the range of between 1.65 and 1.75; and

the aluminium oxynitride layer has a thickness in the range of between 650 and 850 ångströms.

- 19. (New) Glazing according to Claim 14 wherein the oxide layer providing the low-emission and/or solar protection properties is a layer based on at least one of the following (E) through (G):
 - (E) doped tin oxide;
 - (F) is a tin oxide layer containing antimony oxide, the atomic ratio Sb/Sn being in the range of between 0.02 and 0.15;
 - (G) fluorine-doped tin oxide.
- 20. (New) Process for the production of glazing according to Claim 14, wherein the aluminium oxynitaide layer is formed by pyrolysis using gaseous precursors comprising aluminium trichloride or trimethyl aluminium.